

Single and Double Hole Quantum Dots in Strained Ge/SiGe quantum wells

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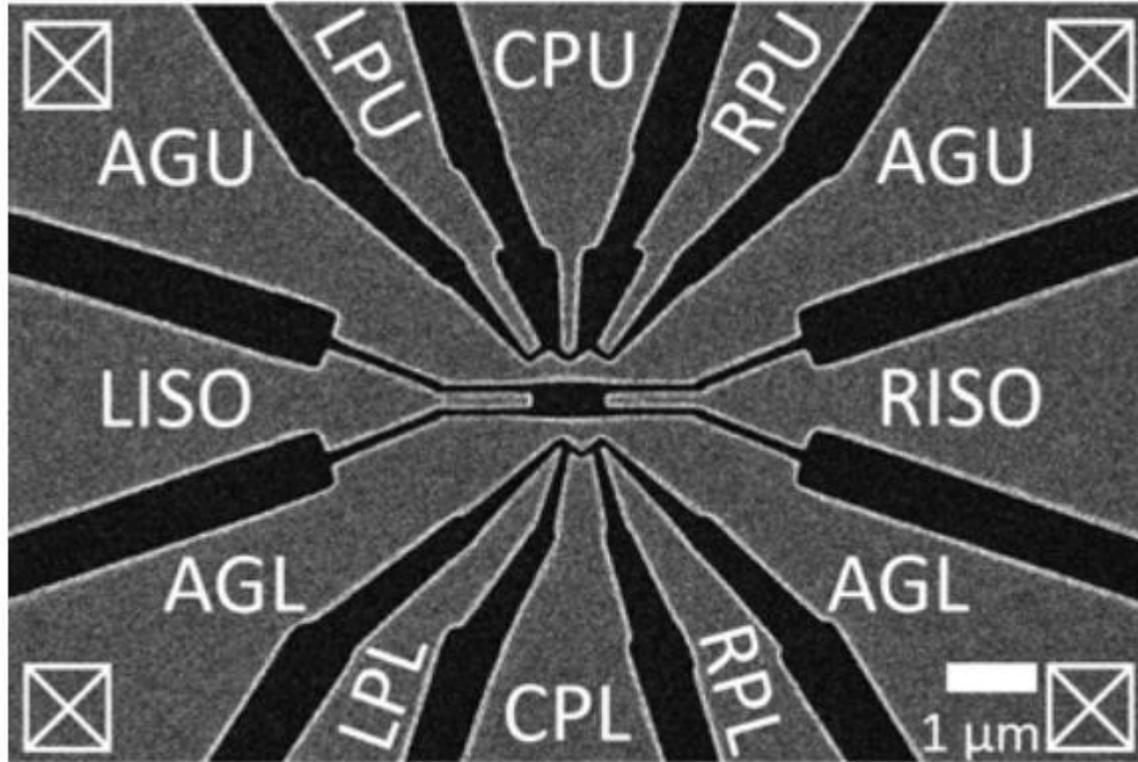
Nanotechnology 30 (2019), 215202

- Silicon as a leading contender for hosting spin-based qubits
 - Long coherence times, isotropic enrichment, CMOS processing
 - Si/SiGe heterostructures with low disorder interface
 - Material related issues, e.g large variation of the valley splitting ($35 - 270 \mu\text{eV}$) [1]
- Ge/SiGe heterostructures
 - Holes as dominant charge carriers -> p-type orbital characters, suppresses qubit decoherence via hyperfine
 - Large heavy-hole and light-hole band splitting (up to 100 meV) -> results from confinement and strain [2]
 - Heavy-hole ground state has no degenerate states
 - EDSR possible due to large cubic Rashba spin-orbit coupling strength -> simplified device design
 - Large g -factor (up to $g \sim 28$)
- In this paper
 - Single and double quantum dots in planar Ge/SiGe using a single layer gate layout
 - Hole effective mass of $m^* \sim 0,08 m_0$

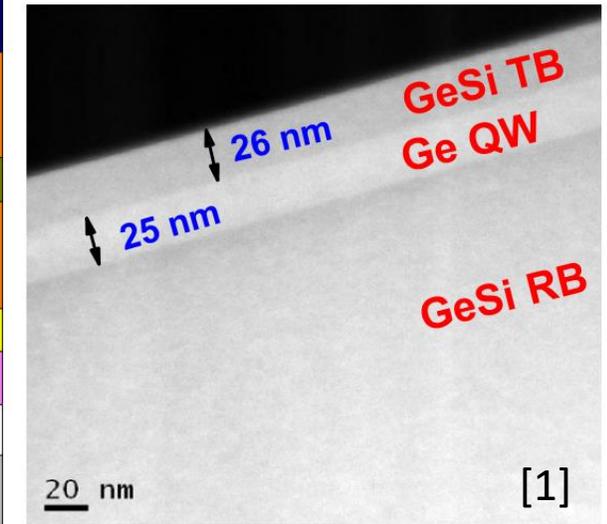
[1] Borselli et al., APL 98, 123118 (2011)

[2] Moriya et al., PRL 113, 086601 (2014)

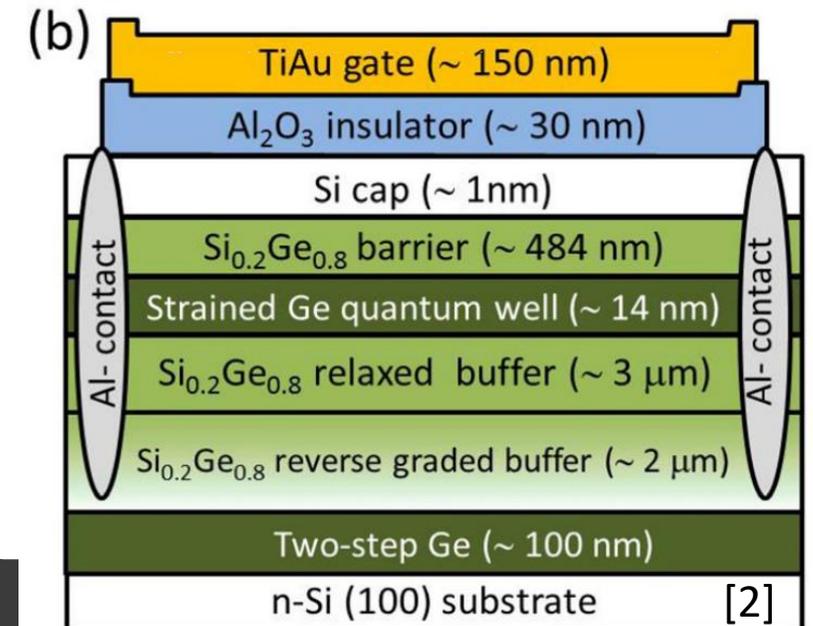
Device and Heterostructure



Al_2O_3 (90 nm)
$\text{Ge}_{0.85}\text{Si}_{0.15}$
Top Barrier (t nm)
Ge QW (25 nm)
$\text{Ge}_{0.85}\text{Si}_{0.15}$
Relaxed Buffer (3 μm)
HT-Ge Buffer (100 nm)
LT-Ge Buffer (200 nm)
Si Buffer (200 nm)
p ⁻ -Si(100) substrate



- Here: LT-Ge: 100 nm, HT-Ge: 200 nm, TB: 70 nm
- Q1: 15 % Si, 100 nm Al_2O_3 , mobility $\mu > 10^5$ cm²/Vs
- Q2: 28 % Si, 24 nm Al_2O_3 + 1 nm HfO_2 , mobility $\mu > 10^5$ cm²/Vs
- Gate design inspired by designs used in Si/SiGe electron systems

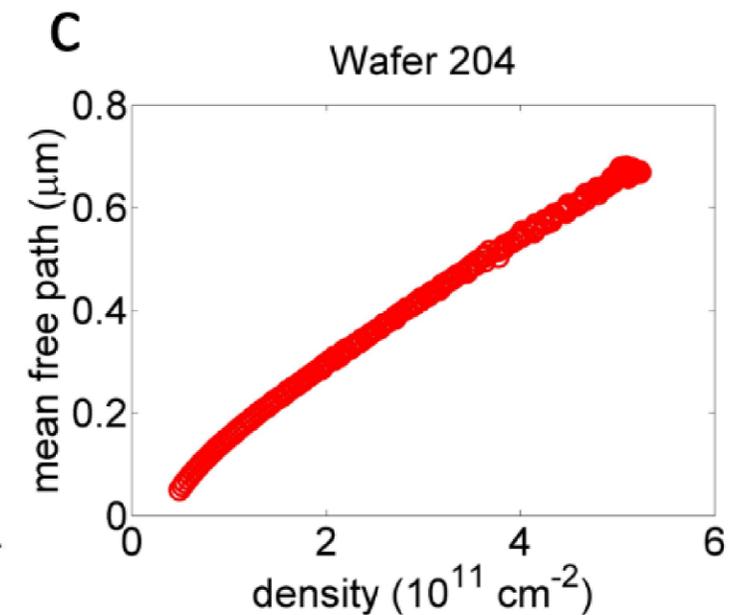
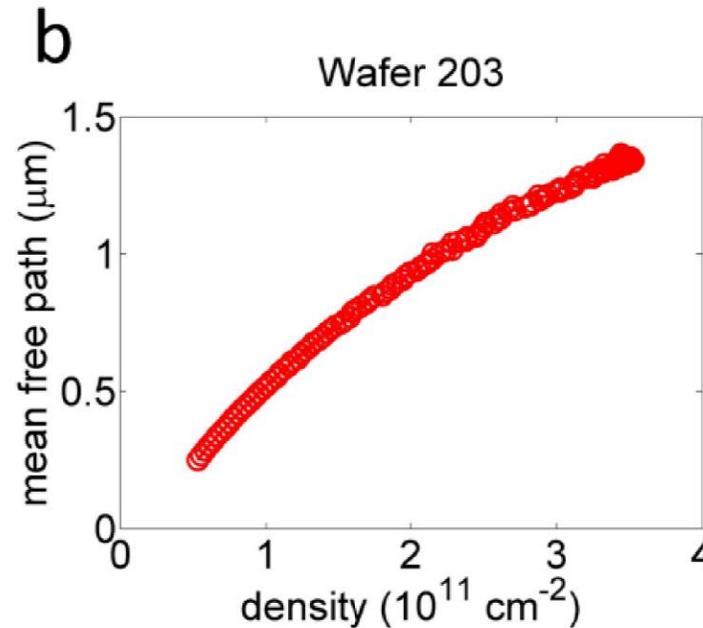
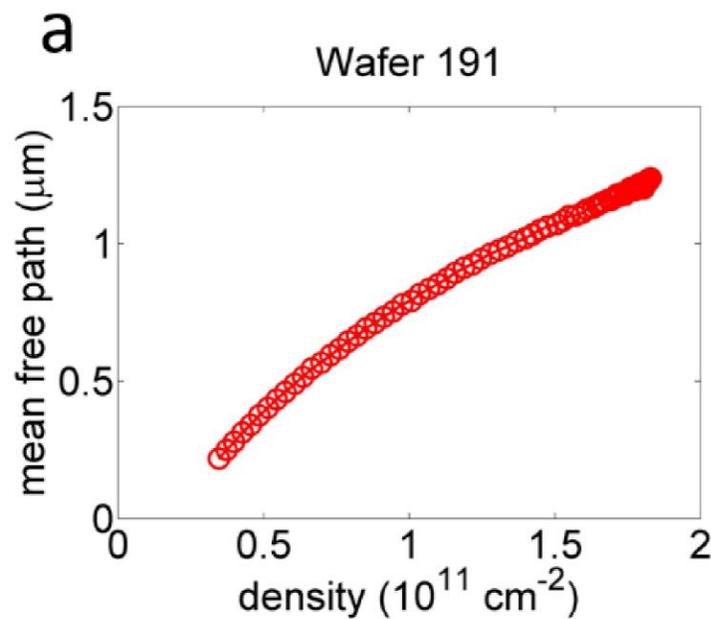


[1] Su et al., Phys Rev Mat. 1 044601 (2017)

[2] Laroche et al., APL 108, 233504 (2016)

Hall Bar Measurements I

- Longitudinal and Hall resistance measured in 4He cryostat with variable temperature
- Mean free path from mobility measurements
 - $\mu \geq 6 \times 10^4 \text{ cm}^2/\text{Vs}$
 - High quality samples, low disorder



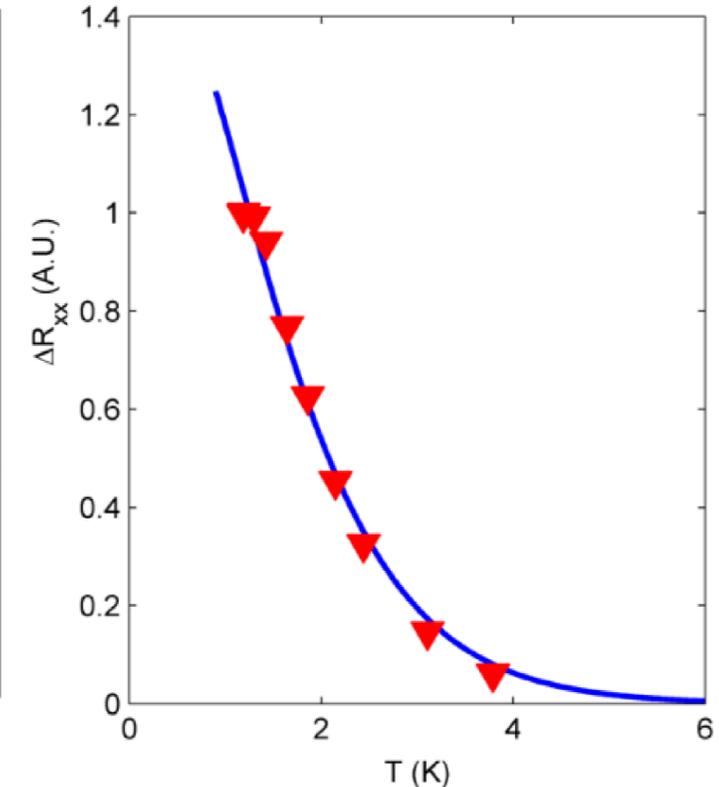
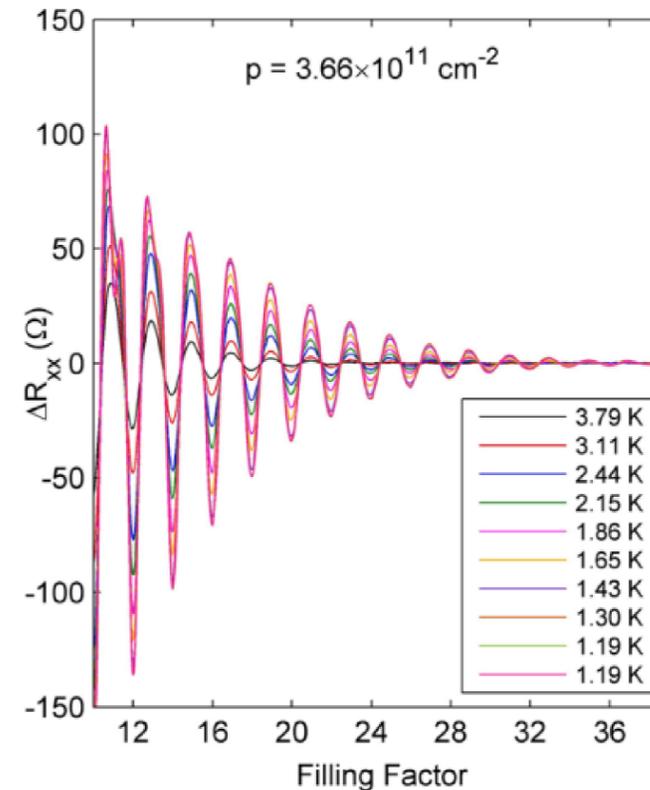
Hall Bar Measurements II

- Magnetoresistance data reveals Shubnikov-de Haas oscillations
 - Shows low disorder of material
 - Inverse proportional to temperature
- Extract amplitudes of even filling factor and trace temperature dependence to extract effective mass at various densities

$$\Delta R_{xx} \propto \frac{2\pi^2 \frac{k_B T}{\Delta E}}{\sinh \left[2\pi^2 \frac{k_B T}{\Delta E} \right]}$$

with $\Delta E = \hbar e B / 2\pi m^*$

- Yields a hole effective mass of $m^* \sim 0.08 m_0$
 - Note: electron effective mass in GaAs: $m^* \sim 0.067 m_0$
- Large spacial extent -> enhanced tunnel couplings, facilitation of qubit-qubits interaction, larger lithography



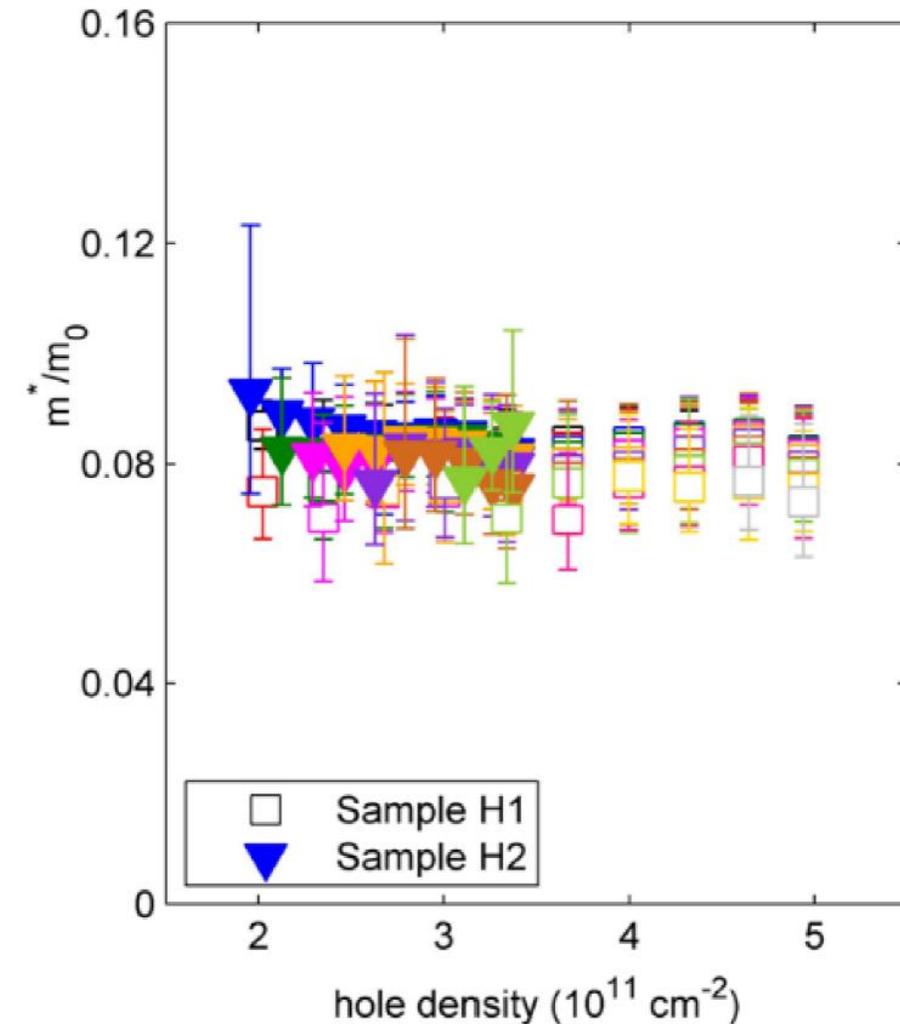
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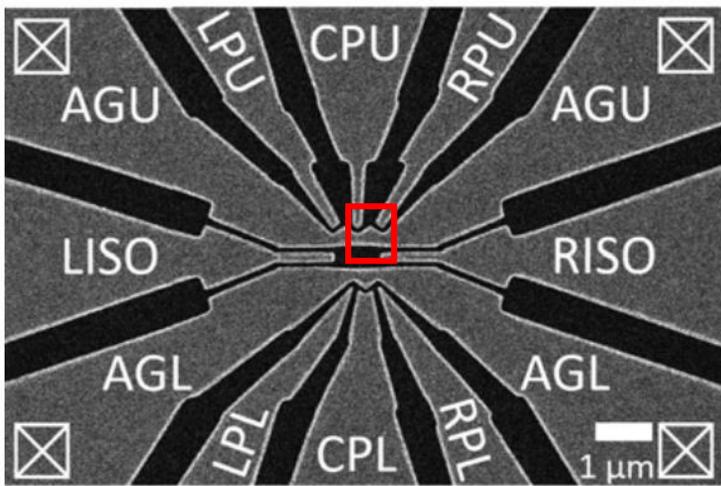
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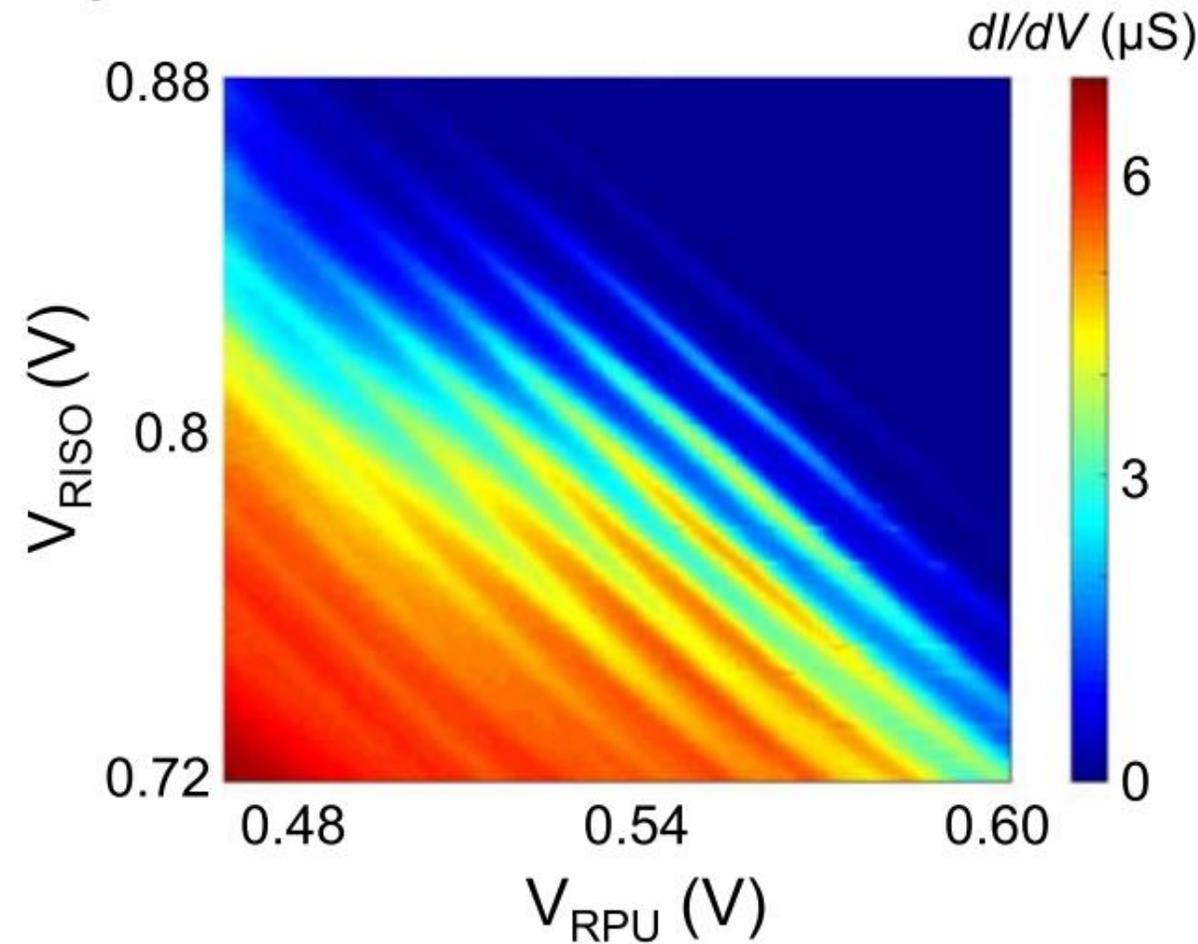
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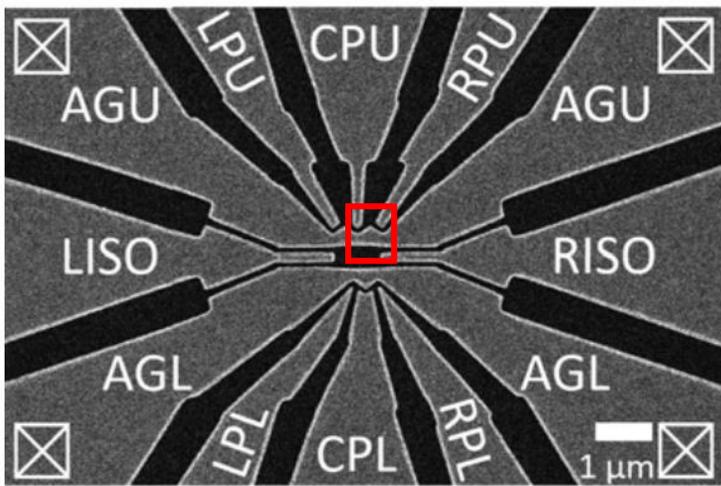
Single Dot I



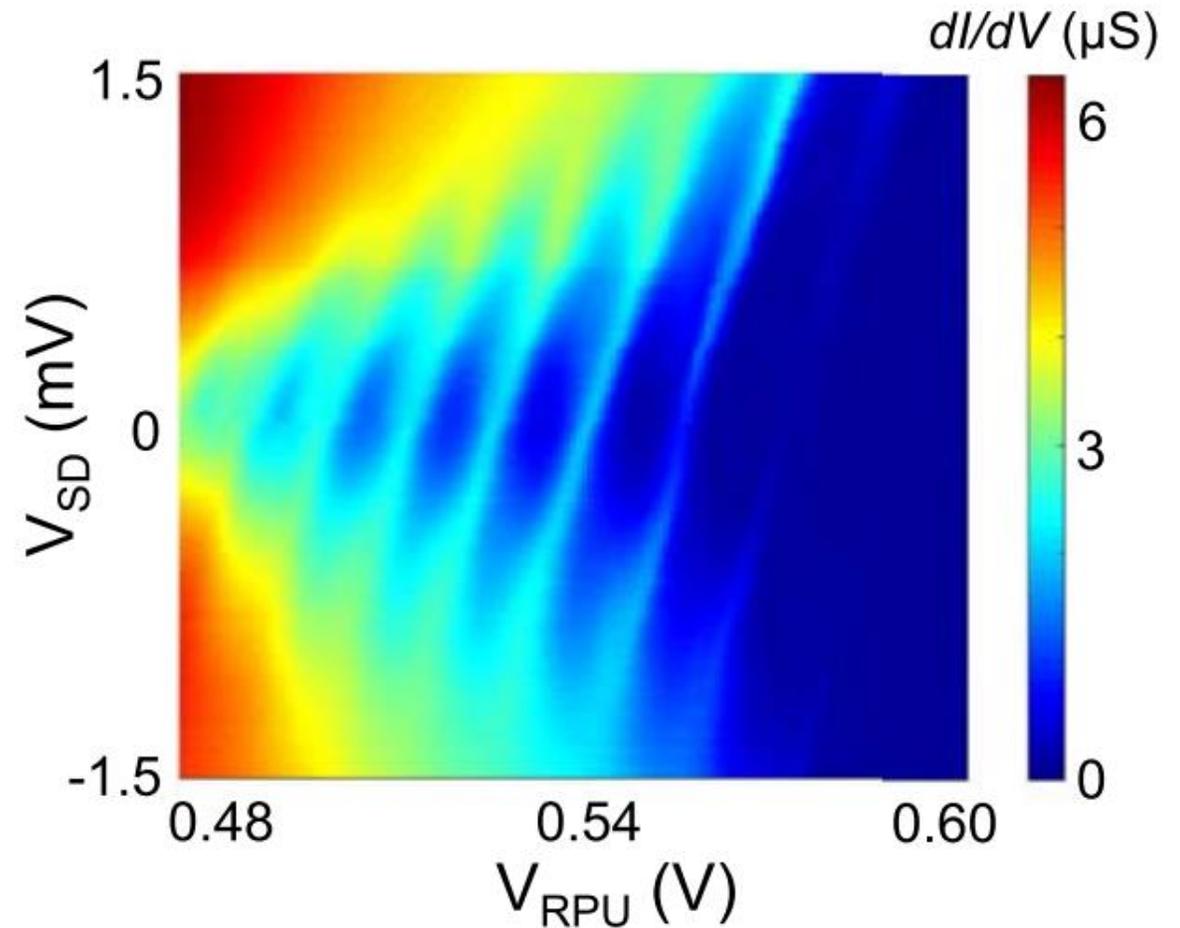
- Measurements performed in dilution refrigerator ($T \sim 30$ mK)
- Accumulation gates: -0.4 – -1.6 V; AC bias: $100 \mu\text{V}$ at 1333 Hz
- CPU fixed, RISO and RPU sweep \rightarrow diagonal lines visible
 - Coulomb oscillations corresponding to removal of individual holes
- Broadening due to highly transparent tunnel barriers, not experimental parameters (temperature, voltage bias, ...)
 - Excludes possibility to see excited states
 - Consistent with simulations (later slides)



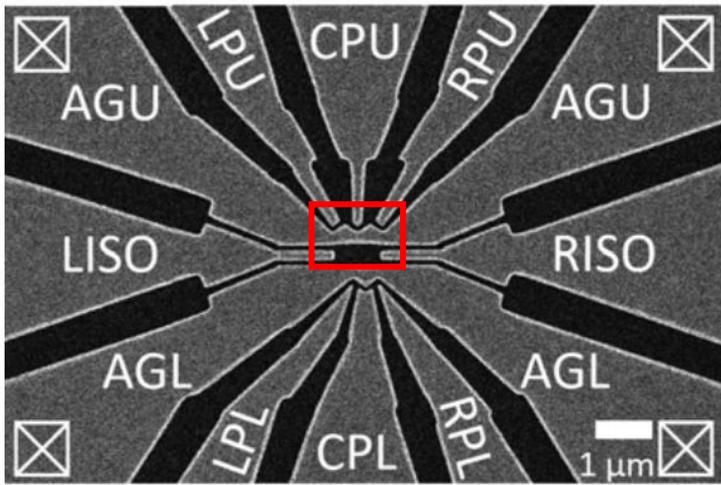
Single Dot II



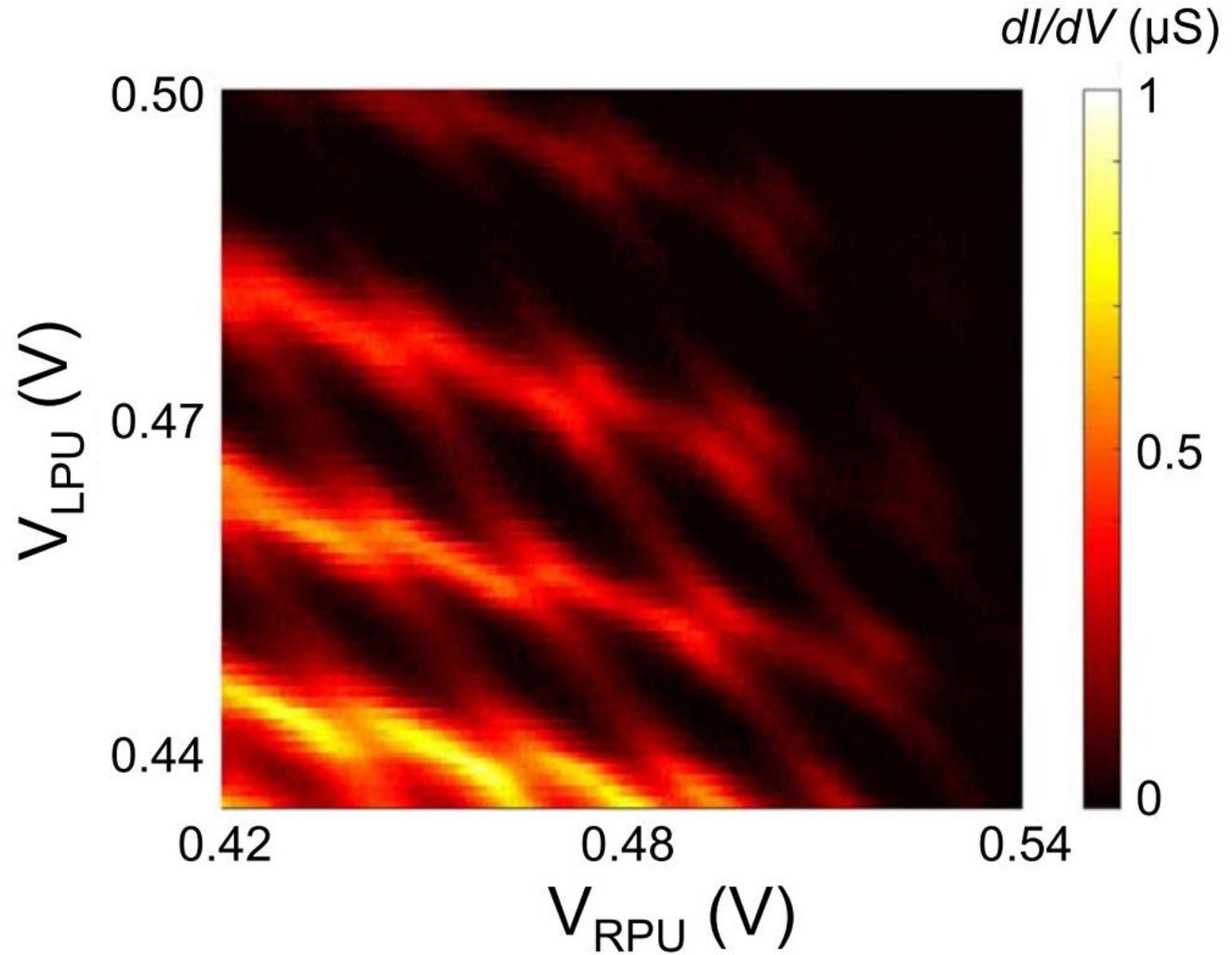
- CPU and RISO fixed, SD and RPU sweep -> Coulomb diamonds
- Diamonds widen -> increasing charging energy -> low occupancy regime
- Capacitance $C_{tot} = \frac{Q}{V} = 92.8$ aF (with V extracted Coulomb oscillation period)
 - Charging energy $E_c = \frac{e^2}{C_{tot}} = 1.7$ meV
 - Consistent with height of Coulomb diamonds



Double Dots

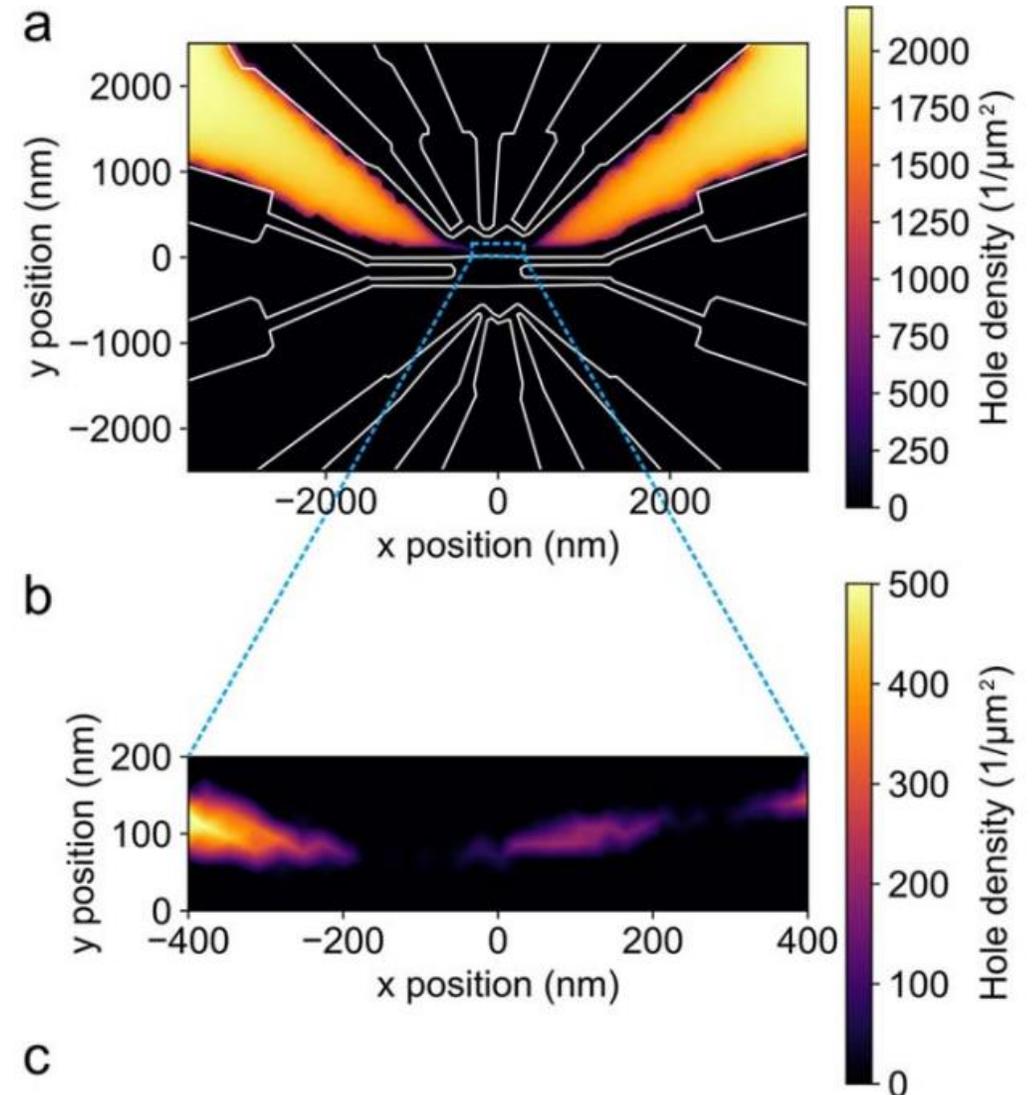


- Device tuneable into double dot regime
 - Visible in stability diagram
- Note: no additional voltage needed on CPU, potential landscape imposed by AGU naturally forms dot

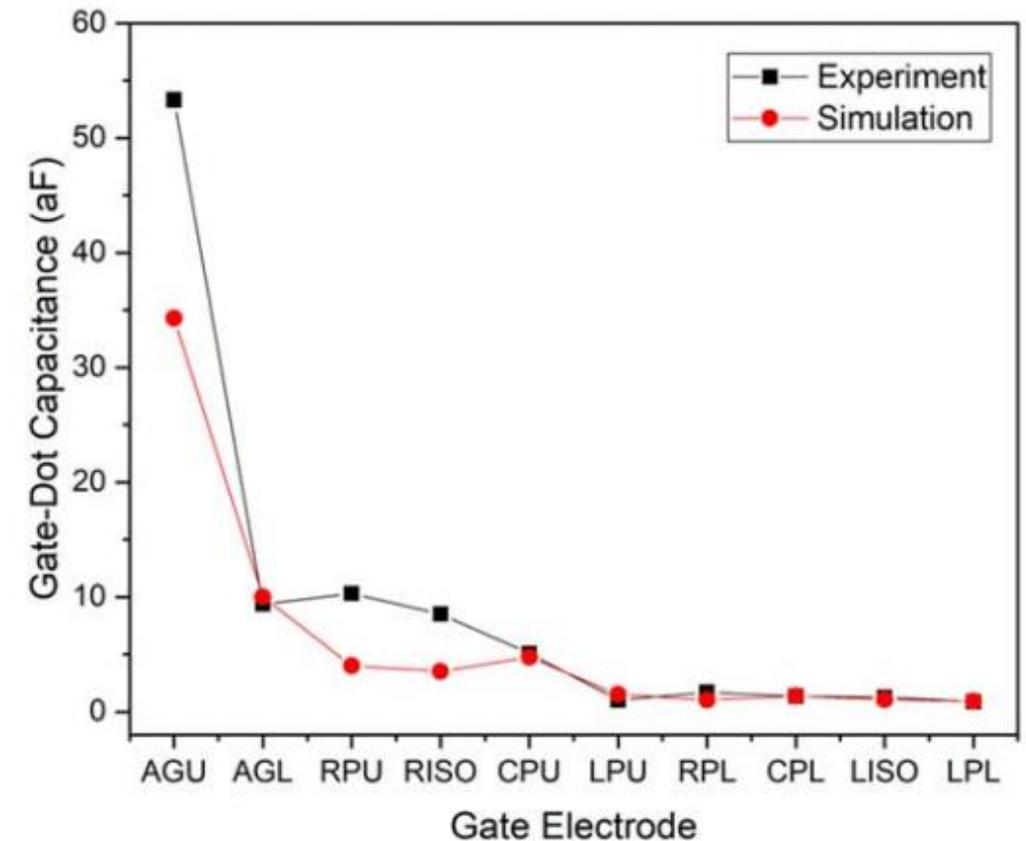


Simulation

- Simulation of device with parameters extracted from SEM images, material stack thickness and dielectric properties
- Gates voltages comparable to actual device (except CPU -> trapped charge in real device)
- Simulation reveals
 - Oblong island -> quantum dot
 - Rapid transition from no charge accumulation to a flooded situation without charge confinement
 - Only few holes possible -> shallow potential
- Further simulations of capacitance -> reasonable agreement with measured capacitances
 - Dot on real device has similar lateral extent



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Conclusion

- Demonstration of single and double hole quantum dots in a Ge/SiGe heterostructure with a single gate layer
- Design similar to Si/SiGe systems
 - Allows direct comparison
- Hall measurement reveal hole effective mass of $m^* \sim 0.08 m_0$
 - Similar to GaAs electron effective mass ($0.067 m_0$)
 - Large wavefunction

